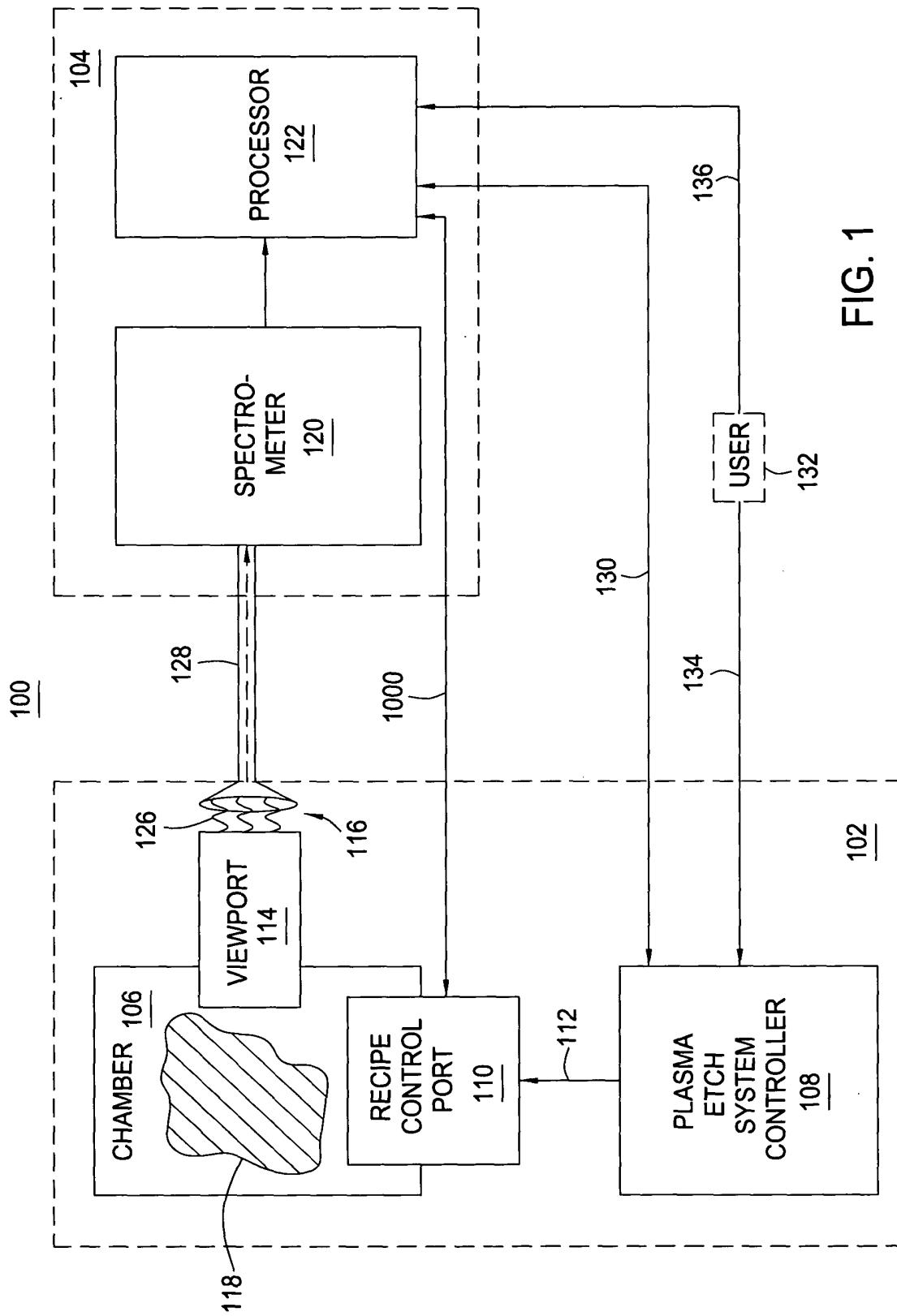


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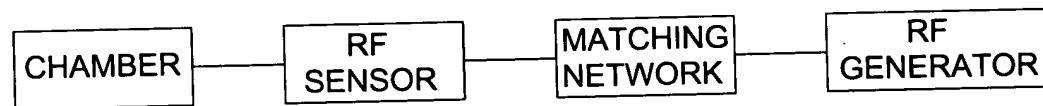


FIG. 2

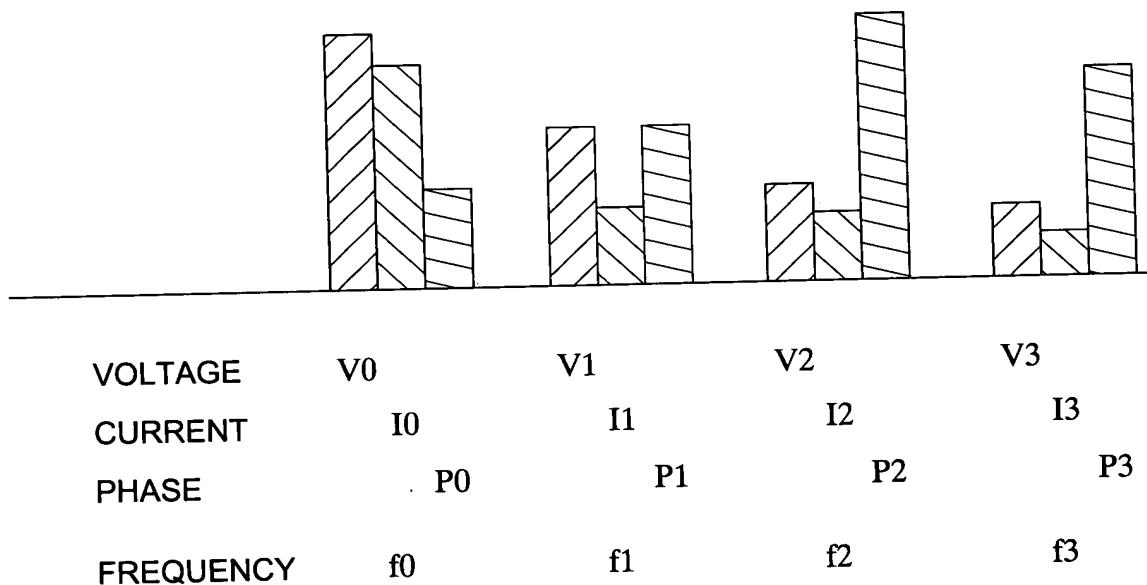


FIG. 4

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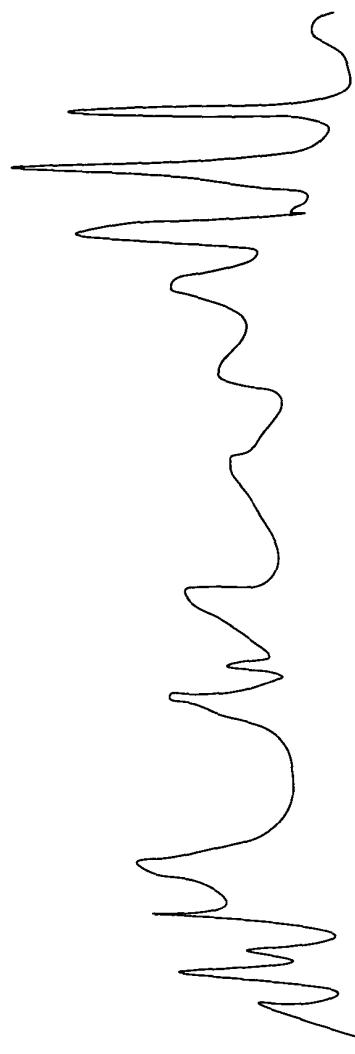


FIG. 3

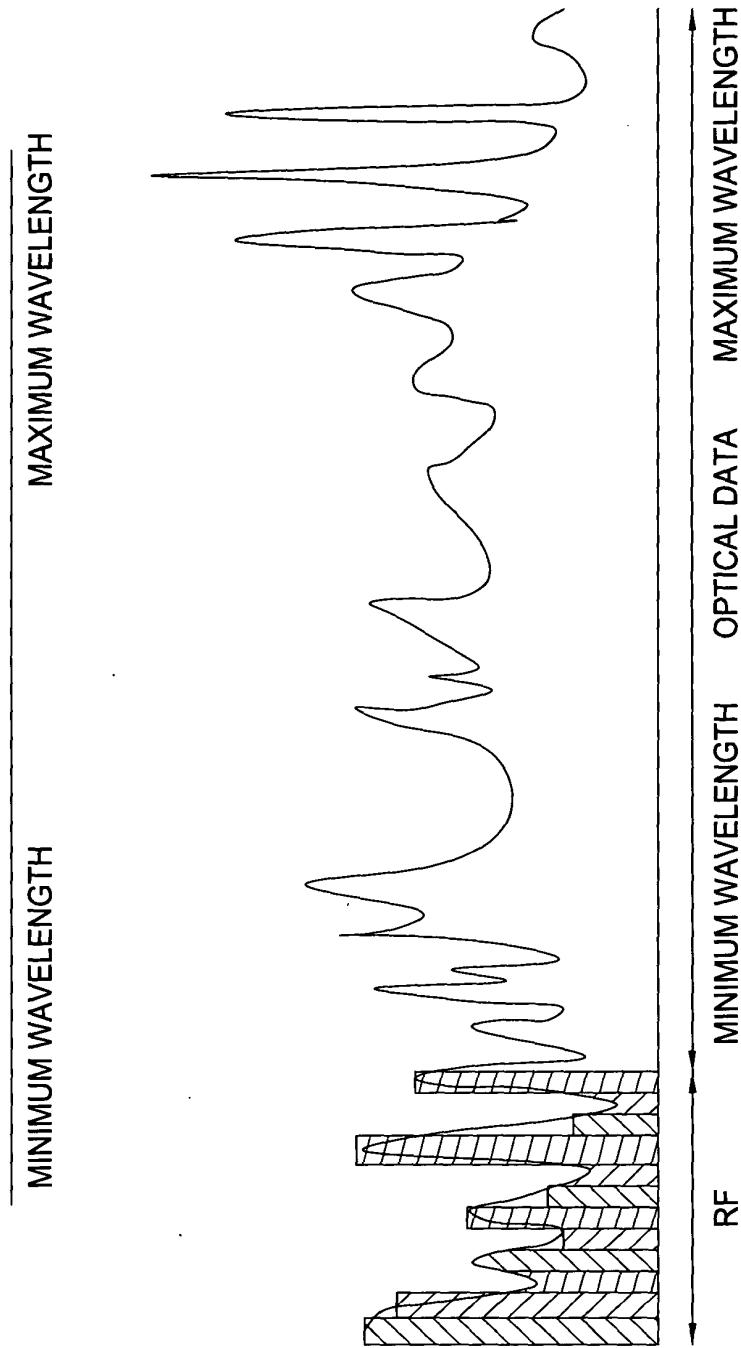


FIG. 5

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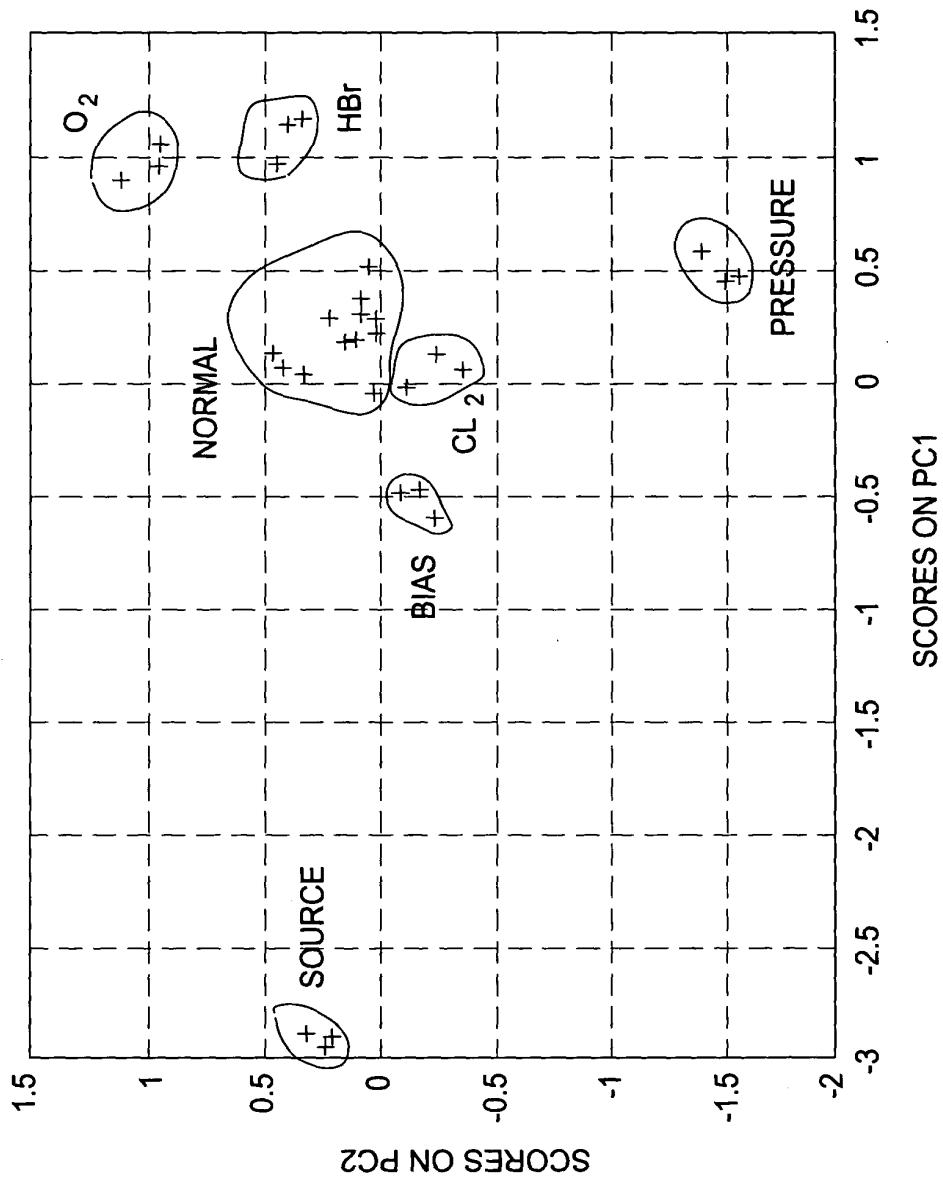


FIG. 6A

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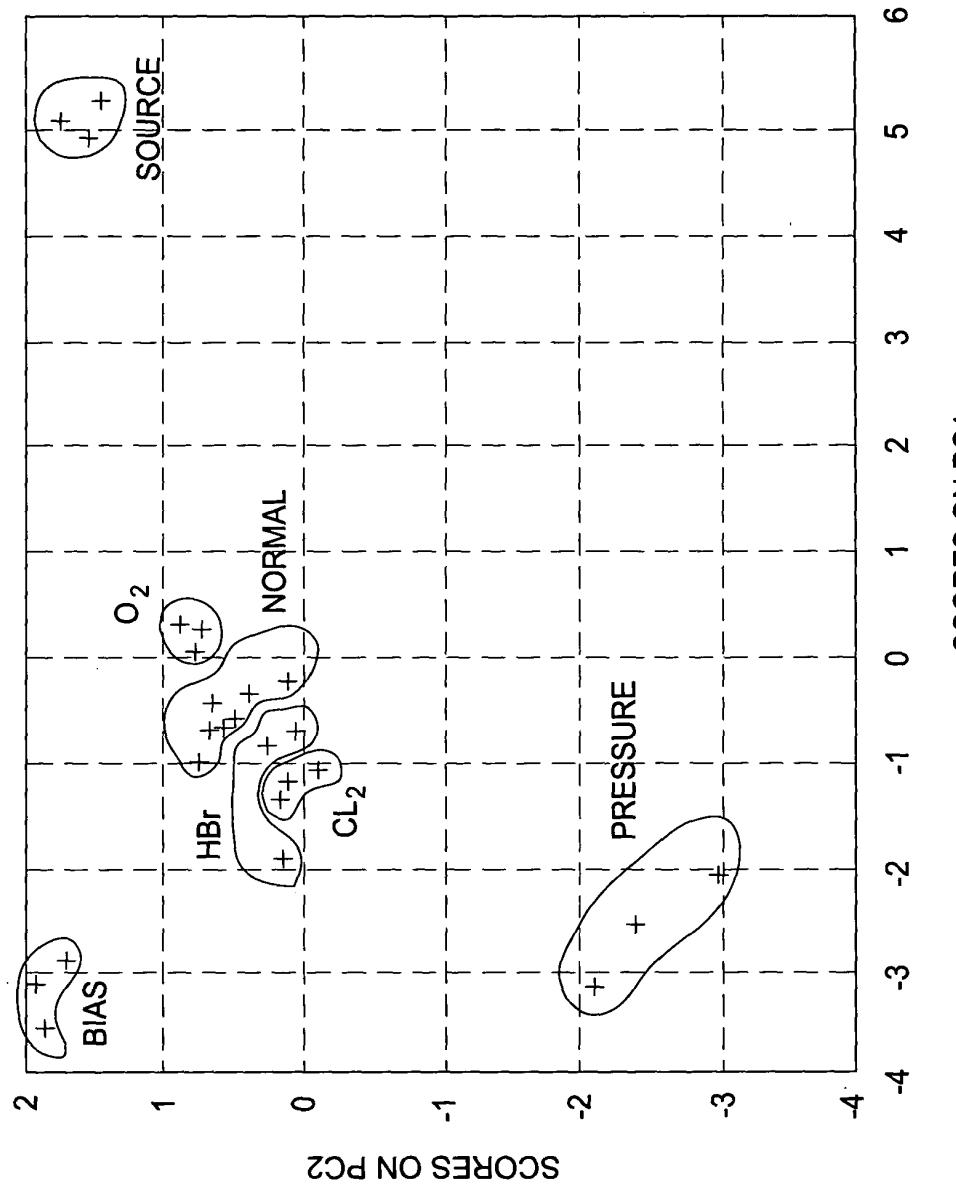
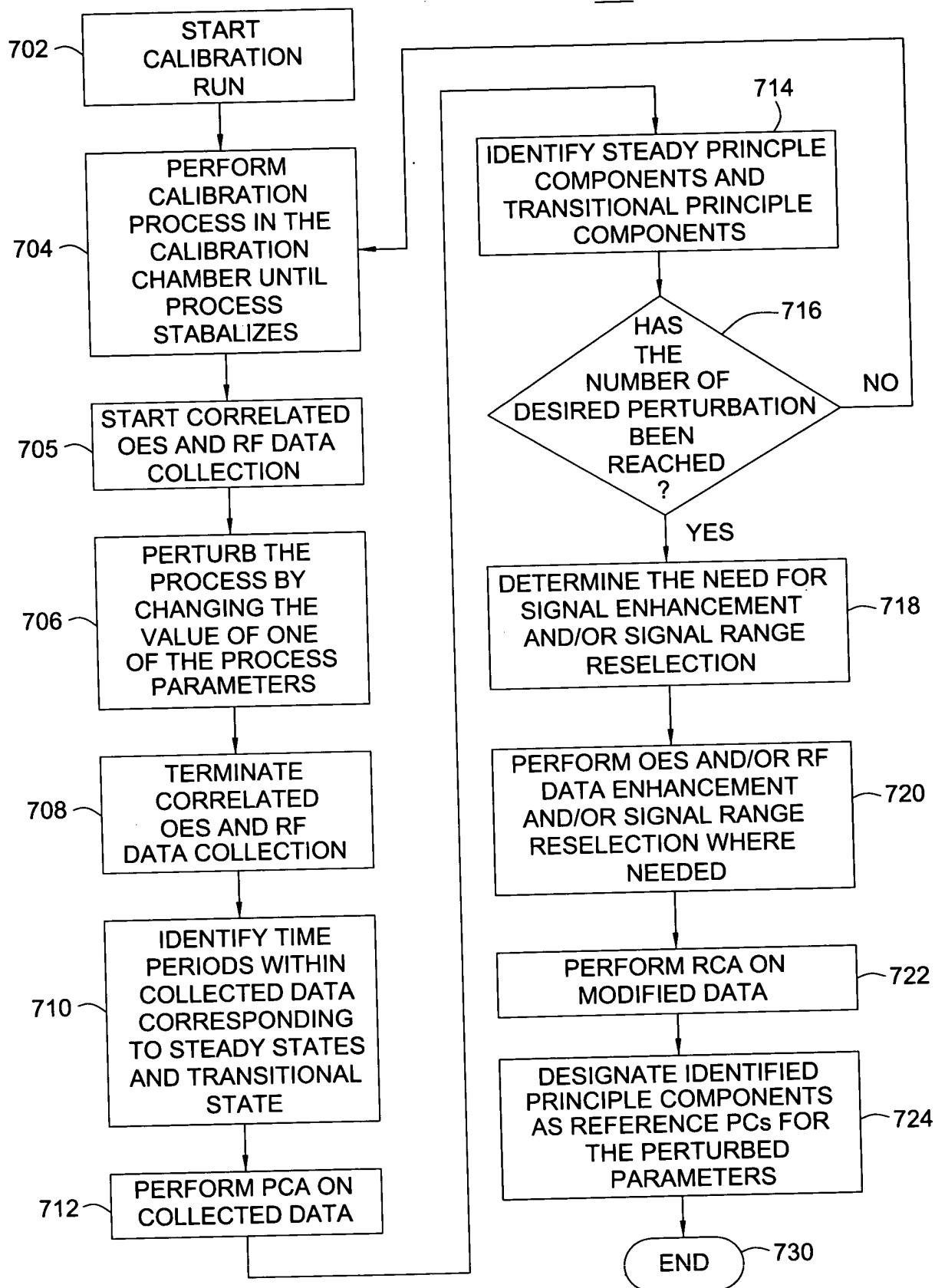


FIG. 6B

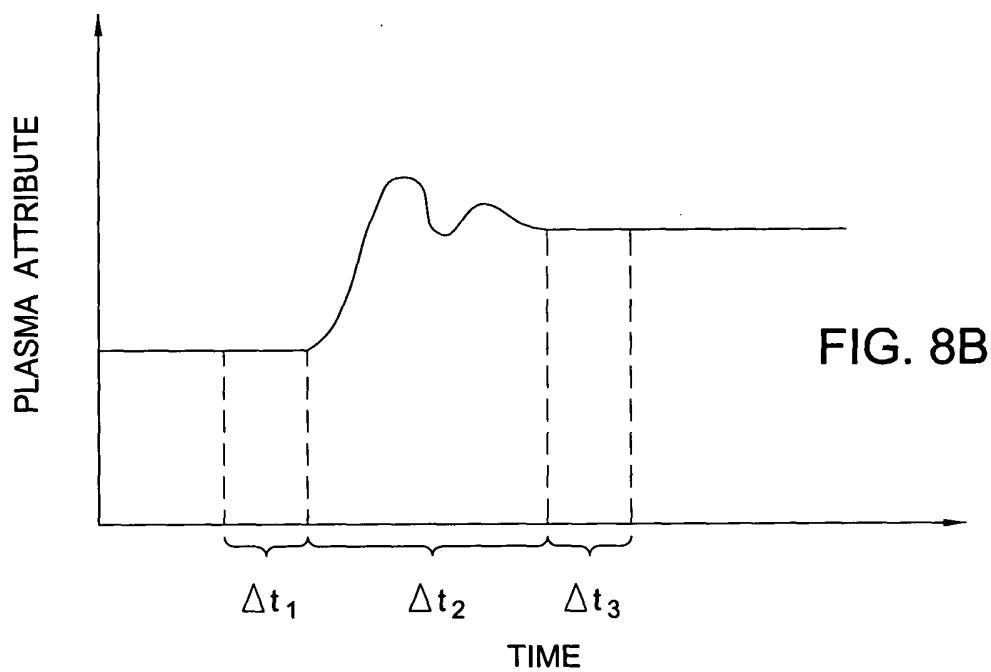
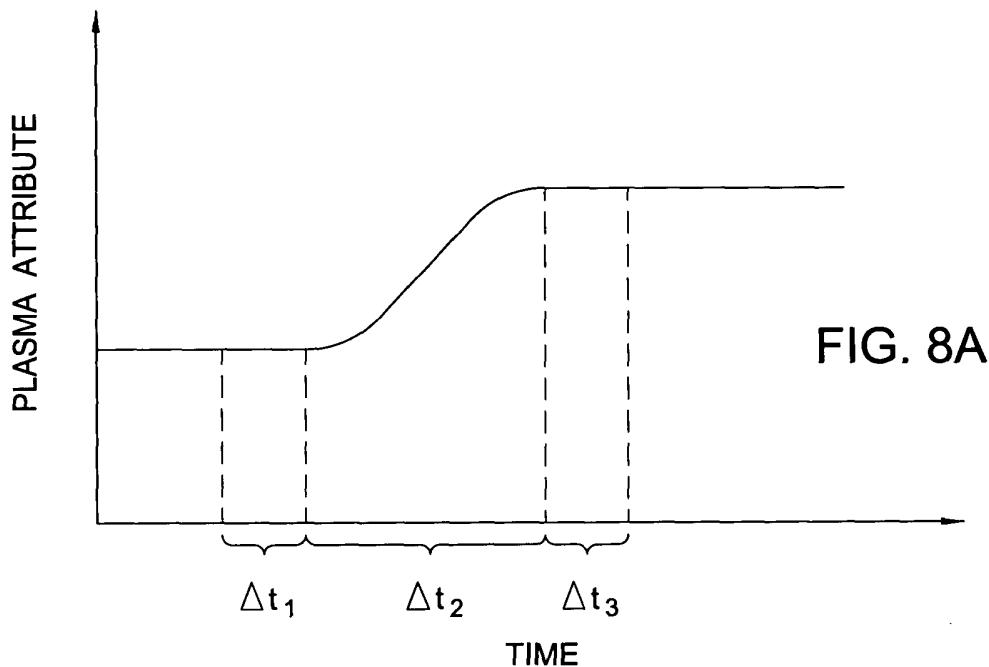
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700

FIG. 7



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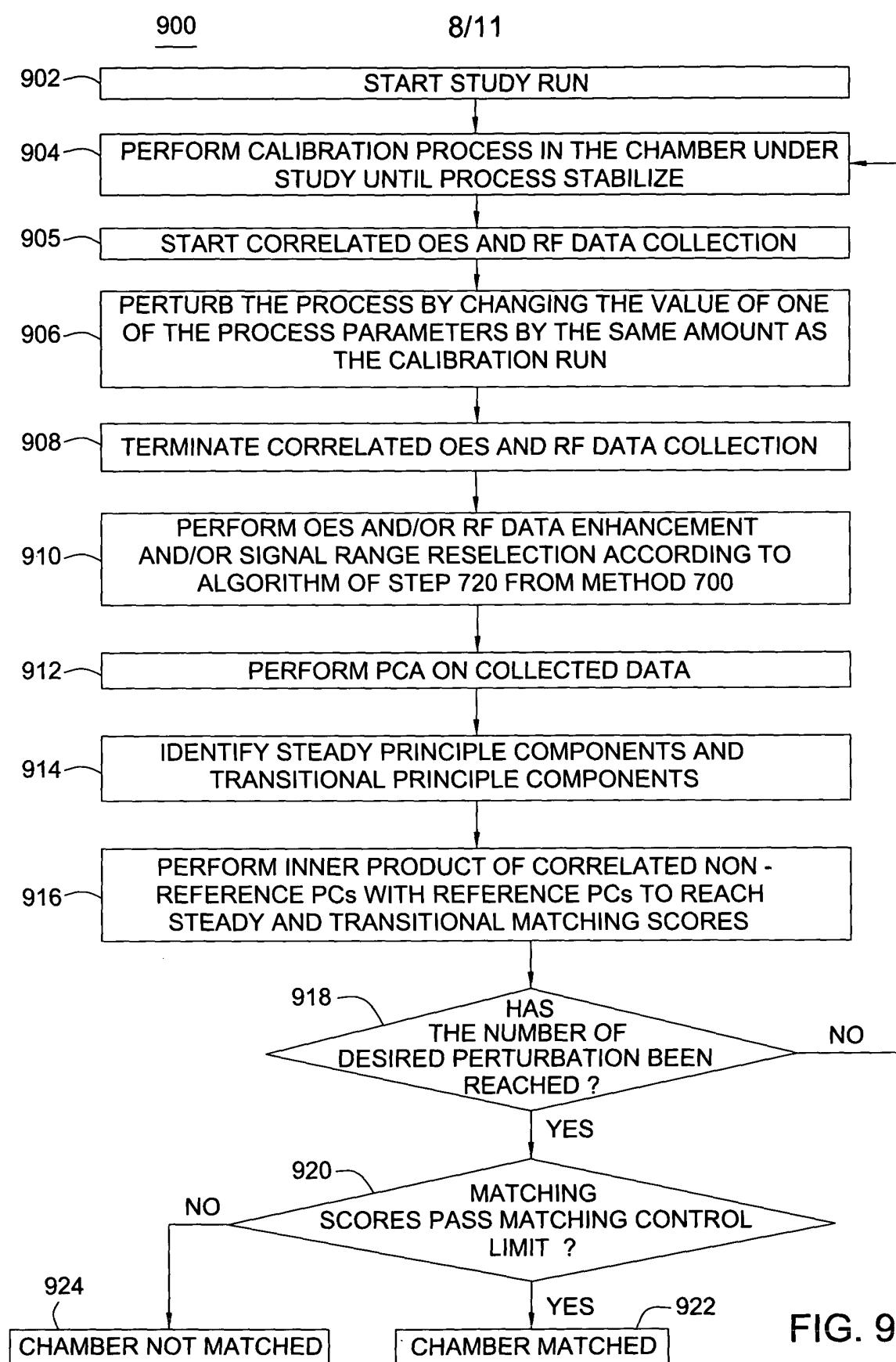


FIG. 9

Atty Dkt. No. AMAT/7938/ETCH/SILICON/JB
Filed: Herewith
Applicant: Davis et al.
Title: METHOD FOR AUTOMATIC DETERMINATION OF
SEMICONDUCTOR PLASMA CHAMBER MATCHING AND
SOURCE OF FAULT BY COMPREHENSIVE PLASMA
MONITORING
Express Mail No.: EV324942792US
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TRANSITIONAL SCORE

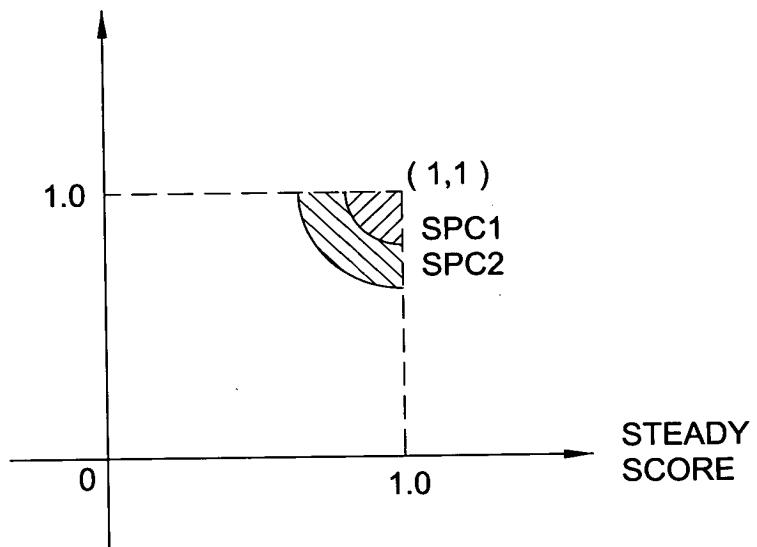
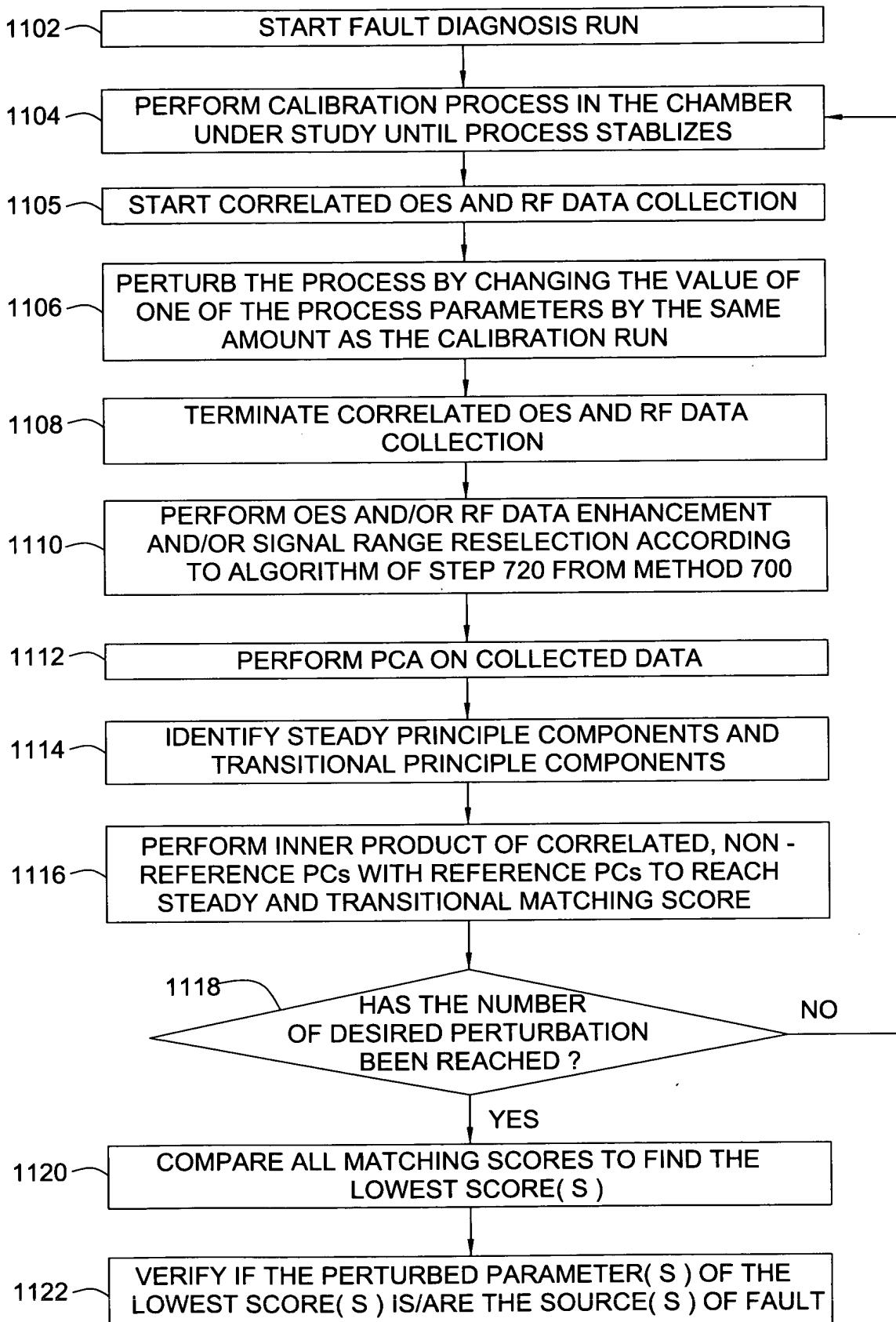


FIG. 10

1100

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FIG. 11



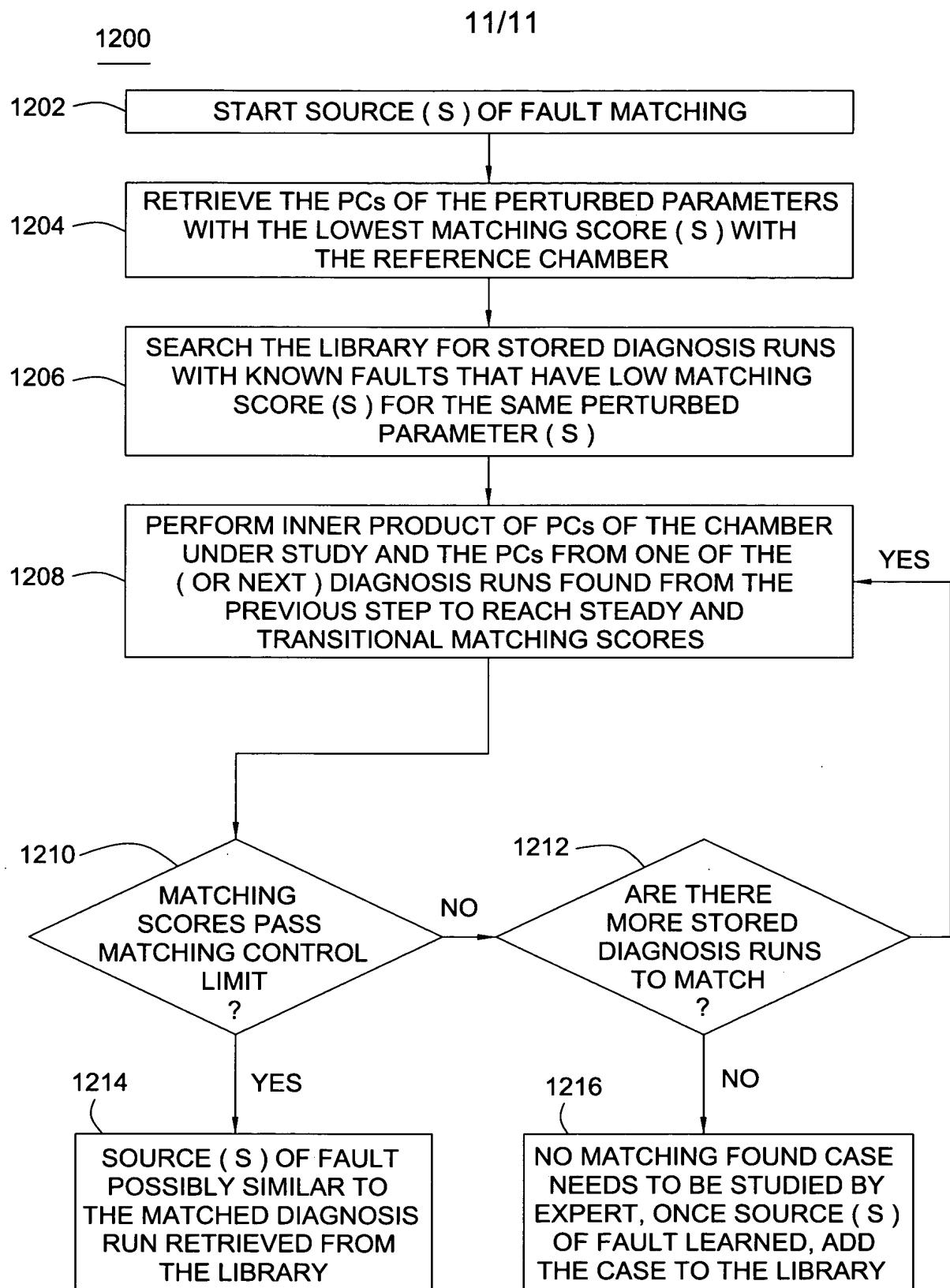


FIG. 12